

ABSTRACT

5 A photomask blank comprising a transparent substrate
 (1), an etching stop film (2), a light-shielding film (3),
 and an etching mask film (4) has on the substrate side a
 reflectance of up to 35% with respect to exposure light. The
 etching stop film (2) consists of a first layer (21) which is
10 disposed contiguous to the substrate and functions as an
 antireflective layer and a second layer (22) functioning as a
 fluorine-base dry etching-resistant layer, one of the first
 and second layers is a layer having compressive stress and
 the other is a layer having tensile stress.

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Fig. 1